



Session Title:	[MoA2] Advanced Growth Techniques – I
Session Date:	July 13 (Mon.), 2026
Session Time:	14:00–15:45
Session Room:	Room A (Baekrok Hall B-1, 1F)
Session Chairs	

[MoA2-1] [Invited]	14:00–14:30
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Remote Epitaxy of Deformable and Stacktronic Devices
Young Joon Hong, Sungkyunkwan University, Korea

[MoA2-2]	14:30–14:45
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Fabrication of Wafer-Scale Freestanding GaN Membrane Utilizing Transfer-Free Thin Amorphous Carbon Layer via MOCVD-Based Remote Epitaxy
Joonghoon Choi, Wonkwang Yang, Chang Soo Kim, Junhyun Bae, and Young Joon Hong, Sungkyunkwan University, Korea

[MoA2-3]	14:45–15:00
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Remote Epitaxy of α -Ga₂O₃ via Polycrystalline MoS₂
Gyeong Ryul Lee and Roy. B. Chung, Kyungpook National University, Korea

[MoA2-4]	15:00–15:15
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MOCVD of GaN and AlGaIn/GaN Heterostructures on Si(001) by Wafer-Scale MoS₂ Templates
Seung Hoon Lee¹, Chen Chen¹, Brian M. Bersch², and Joan M. Redwing¹, ¹ Pennsylvania State University, USA, ² Northrop Grumman Mission Systems, USA

[MoA2-5]	15:15–15:30
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InGaIn Quantum Wells Grown on Spatially Patterned Substrates – Towards the 3D Laser Emitters
Grzanka Ewa, Grzanka Szymon, Robert Czernecki, Mikolaj Grabowski, Roman Hrytsak, Artur Lachowski, Julita Smalc-Koziorowska, and Michal Leszczynski, Institute of High Pressure Physics, Poland

[MoA2-6]	15:30–15:45
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Room-Temperature Continuous-Wave III–V/Si PhC Lasers on SOI Using Selective Lateral Heteroepitaxy
Xingyu Yang, Yao Chen, Jinglong Chen, Siyuan Yu, and Yu Han, Sun Yat-sen University, China